

# Revisiting DRAM Read Disturbance

Identifying Inconsistencies Between  
Experimental Characterization and  
Device-Level Studies

**Haocong Luo**

**İsmail Emir Yüksel**

**Ataberk Olgun**

**A. Giray Yağlıkçı**

**Onur Mutlu**

**ETH Zurich**

VTS' 25

28 April 2025

# Executive Summary

---

- **Goal:** Align and cross-validate the **experimental characterization** of DRAM read disturbance (RowHammer and RowPress) with the error mechanisms modeled by **device-level simulation**
  - **Challenge:** Gap between real-chip characterization and device-level mechanisms due to low-level DRAM array layout (i.e., true- and anti-cells)
- **Key Methodology:**
  - Extract key device-level read disturbance mechanisms from prior works
  - Reverse-engineer the true- and anti-cells layout of real DRAM chips
  - Perform real-chip characterization that directly match the access and data patterns studied in device-level works
- **Key Inconsistencies:**
  - For Double-Sided RowHammer, experimental characterization shows bitflips in both directions while device-level mechanisms suggest only 1→0 bitflips will happen
  - For Single-Sided RowPress, experimental characterization shows overwhelmingly 1→0 bitflips while device-level mechanisms suggest both kinds of bitflips will happen

# Outline

---

## ■ **Background**

- Key DRAM Organization & Operation
- DRAM Read Disturbance Phenomena: RowHammer & RowPress

## ■ **Device-Level DRAM Read Disturbance Mechanisms**

## ■ **Real-Chip Characterization Methodology**

- Reverse Engineering of True- and Anti-Cell Layout

## ■ **Real-Chip Characterization Results**

- Inconsistency I: Initial Bitflip Direction of Double-Sided RowHammer
- Inconsistency II: Bitflip Count of Double-Sided RowHammer
- Inconsistency III: Bitflip Direction of Single-Sided RowPress

## ■ **Hypotheses**

## ■ **Conclusion**

---

# Outline

---

## ■ **Background**

- Key DRAM Organization & Operation
- DRAM Read Disturbance Phenomena: RowHammer & RowPress

## ■ **Device-Level DRAM Read Disturbance Mechanisms**

## ■ **Real-Chip Characterization Methodology**

- Reverse Engineering of True- and Anti-Cell Layout

## ■ **Real-Chip Characterization Results**

- Inconsistency I: Initial Bitflip Direction of Double-Sided RowHammer
- Inconsistency II: Bitflip Count of Double-Sided RowHammer
- Inconsistency III: Bitflip Direction of Single-Sided RowPress

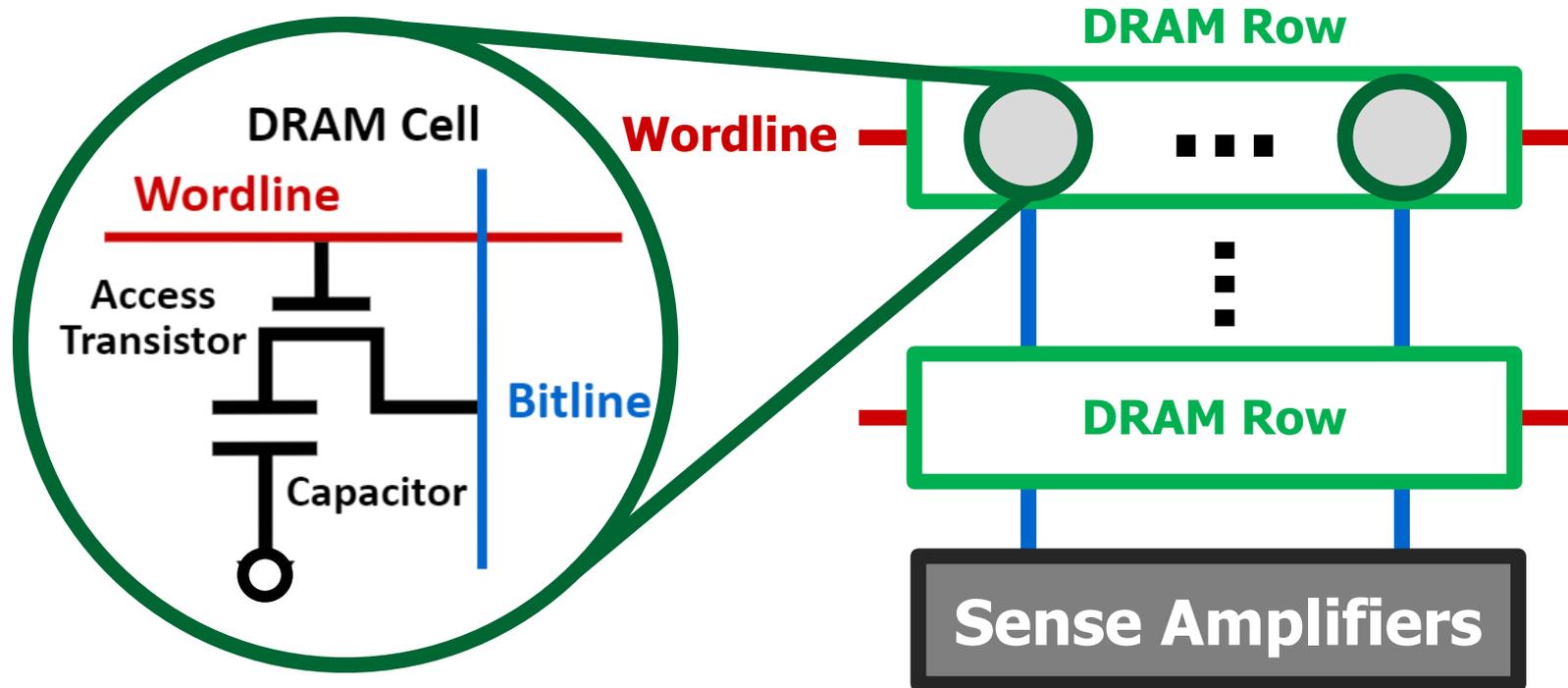
## ■ **Hypotheses**

## ■ **Conclusion**

---

# Background – DRAM Organization I

- **DRAM is the prevalent technology for main memory**
  - A **DRAM cell** stores one bit of information in a leaky capacitor
  - DRAM cells are organized into **DRAM rows**
  - Data are read from DRAM cells at **row-granularity** using **Sense Amplifiers**



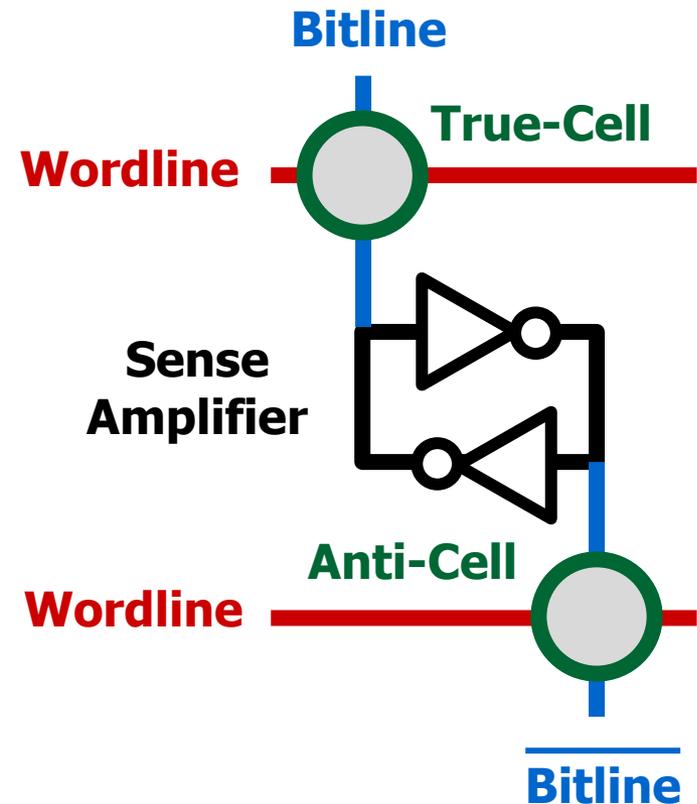
# Background – DRAM Organization II

## ■ True-Cell and Anti-Cell

- The sense amplifier is a differential amplifier
- A DRAM cell can represent a logical 1 by storing either positive or negative charge depending on if it is connected to Bitline or Bitline

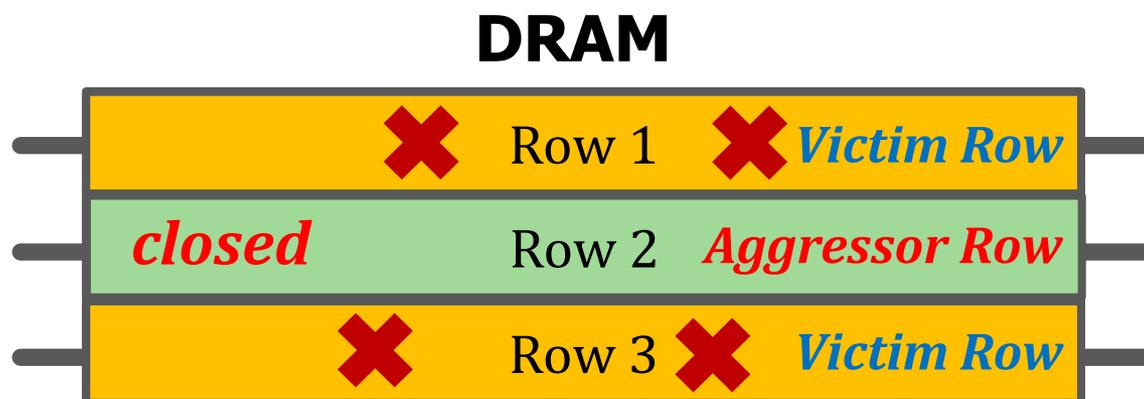
- **True-cell:** Represents a logical 1 by storing positive charge (i.e.,  $V_{Capacitor} = V_{Core}$ )

- **Anti-cell:** Represents a logical 1 by storing negative charge (i.e.,  $V_{Capacitor} = V_{SS}$ )



# Background – DRAM Read Disturbance I

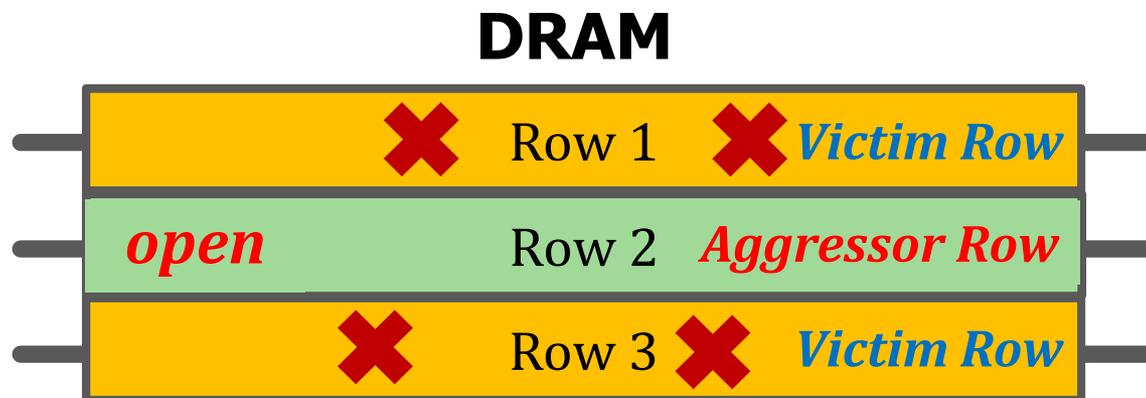
- **Read disturbance in DRAM breaks memory isolation**
  - Accessing a DRAM row (aggressor row) disturbs the integrity of data stored in DRAM cells of other **unaccessed** rows (victim rows), causing bitflips
- **Prominent Example I: RowHammer**



Repeatedly **opening (activating)** and **closing** a DRAM row **many times** causes **RowHammer bitflips** in adjacent rows

# Background – DRAM Read Disturbance II

- **Read disturbance in DRAM breaks memory isolation**
  - Accessing a DRAM row (aggressor row) disturbs the integrity of data stored in DRAM cells of other **unaccessed** rows (victim rows), causing bitflips
- **Prominent Example II: RowPress**



Keeping a DRAM row **open for a long time** causes bitflips in adjacent rows **without** requiring as many row activations as RowHammer

# Outline

---

## ■ Background

- Key DRAM Organization
- DRAM Read Disturbance Phenomena: RowHammer & RowPress

## ■ **Device-Level DRAM Read Disturbance Mechanisms**

## ■ Real-Chip Characterization Methodology

- Reverse Engineering of True- and Anti-Cell Layout

## ■ Real-Chip Characterization Results

- Inconsistency I: Initial Bitflip Direction of Double-Sided RowHammer
- Inconsistency II: Bitflip Count of Double-Sided RowHammer
- Inconsistency III: Bitflip Direction of Single-Sided RowPress

## ■ Hypotheses

## ■ Conclusion

---

# Device-Level Read Disturbance Mechanisms

---

## **Key Device-Level Characteristic 1:**

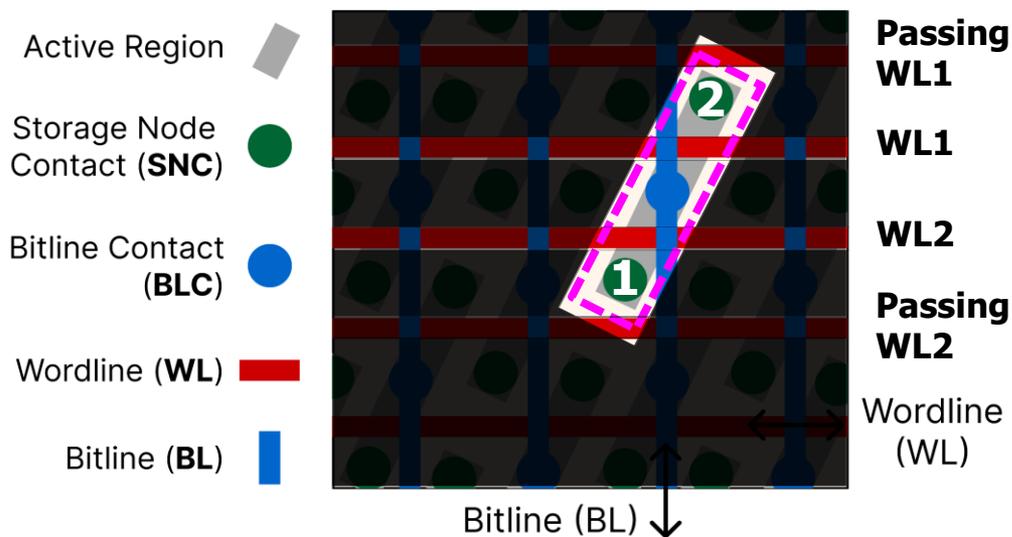
Double-Sided RowHammer should only induce 1→0 bitflips

## **Key Device-Level Characteristic 2:**

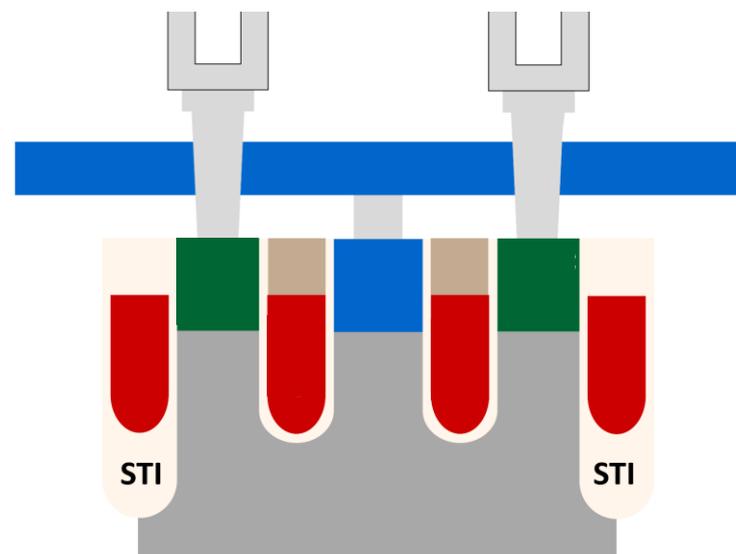
Single-Sided RowPress should induce both  
1→0 and 0→1 bitflips

# Device-Level Mechanisms – Physical Layout

## ■ Modern 6F<sup>2</sup> DRAM cell array layout



**a) Physical Layout of 6F<sup>2</sup> DRAM  
(Top View)**



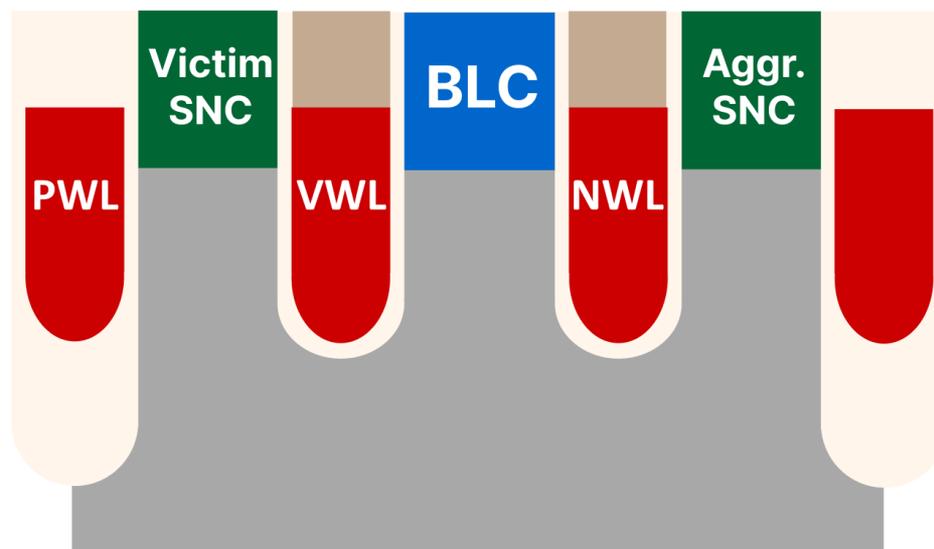
**b) Cross-section of an Active Region  
(Side View, 2 Cells)**

# Device-Level Mechanism – RowHammer I

---

## ■ Key Error Mechanisms of RowHammer

- Trap-assisted Electron Migration [Yang+, EDL'19] [Walker+, TED'21] [Zhou+, IRPS'23]

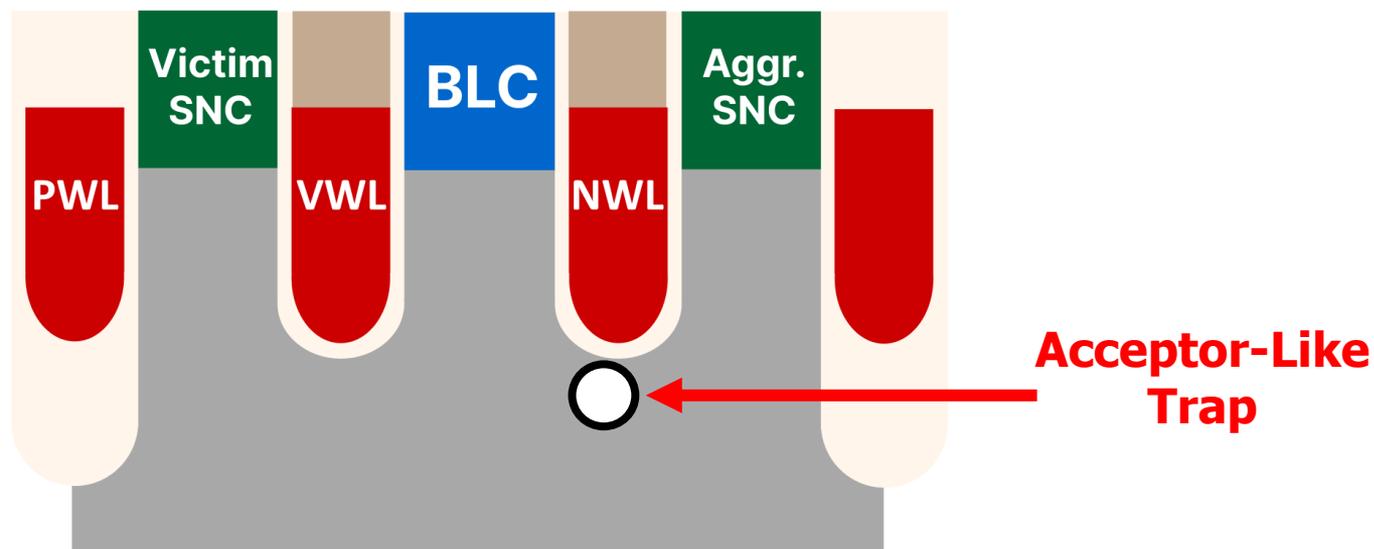


**PWL:** Passing Wordline      **VWL:** Victim Wordline  
**NWL:** Neighboring Wordline (Aggressor)

# Device-Level Mechanism – RowHammer I

## ■ Key Error Mechanisms of RowHammer

- Trap-assisted Electron Migration [Yang+, EDL'19] [Walker+, TED'21] [Zhou+, IRPS'23]

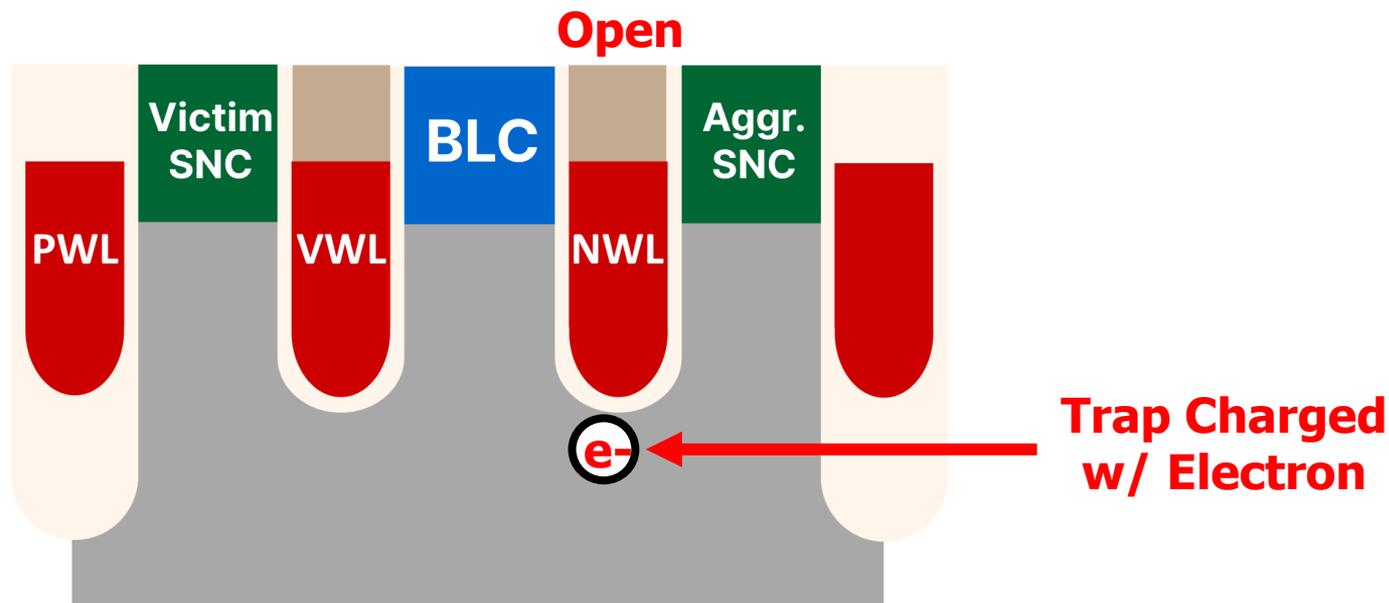


**PWL:** Passing Wordline      **VWL:** Victim Wordline  
**NWL:** Neighboring Wordline (Aggressor)

# Device-Level Mechanism – RowHammer I

## ■ Key Error Mechanisms of RowHammer

- Trap-assisted Electron Migration [Yang+, EDL'19] [Walker+, TED'21] [Zhou+, IRPS'23]
  1. When NWL (aggressor) is open, acceptor-like traps are charged with electrons

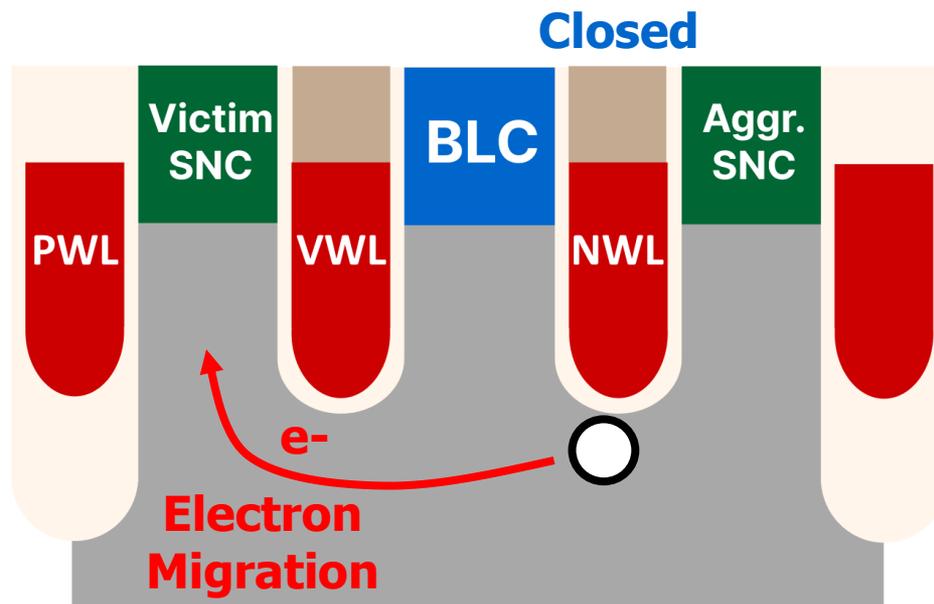


**PWL:** Passing Wordline      **VWL:** Victim Wordline  
**NWL:** Neighboring Wordline (Aggressor)

# Device-Level Mechanism – RowHammer I

## ■ Key Error Mechanisms of RowHammer

- Trap-assisted Electron Migration [Yang+, EDL'19] [Walker+, TED'21] [Zhou+, IRPS'23]
  1. When NWL (aggressor) is open, acceptor-like traps are charged with electrons
  2. When NWL (aggressor) is closed, electrons are emitted from traps and migrate towards the victim cell

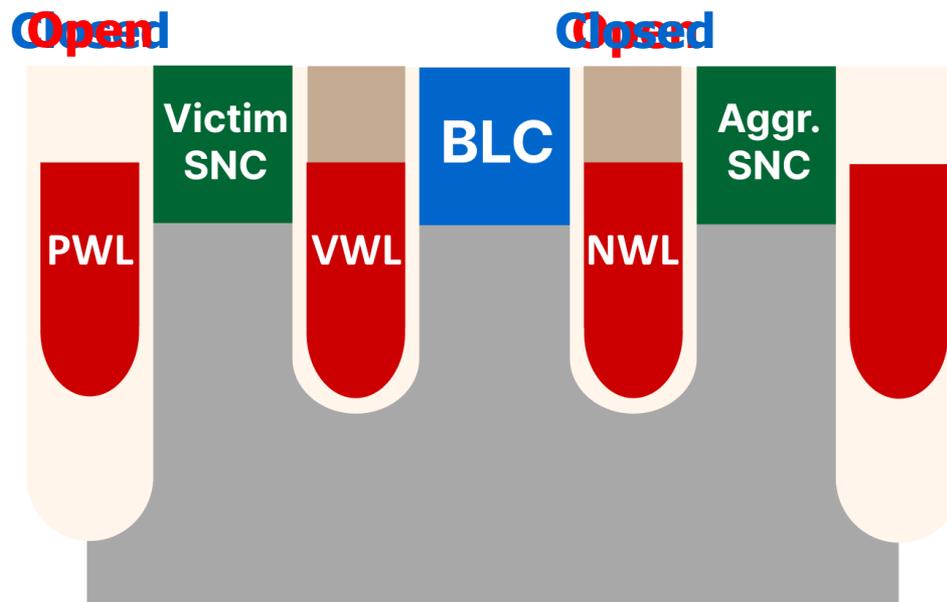


**PWL:** Passing Wordline      **VWL:** Victim Wordline  
**NWL:** Neighboring Wordline (Aggressor)

# Device-Level Mechanism – RowHammer II

## ■ Key Error Mechanisms of RowHammer (Cont'd)

- **Double-Sided RowHammer** is **much more effective** than Single-Sided at inducing bitflips (i.e., require **much fewer aggressor row activations**)
- Both NWL and PWL are aggressors, being opened and closed in an alternating manner, “sandwiching” the victim



**PWL:** Passing Wordline (Aggressor)

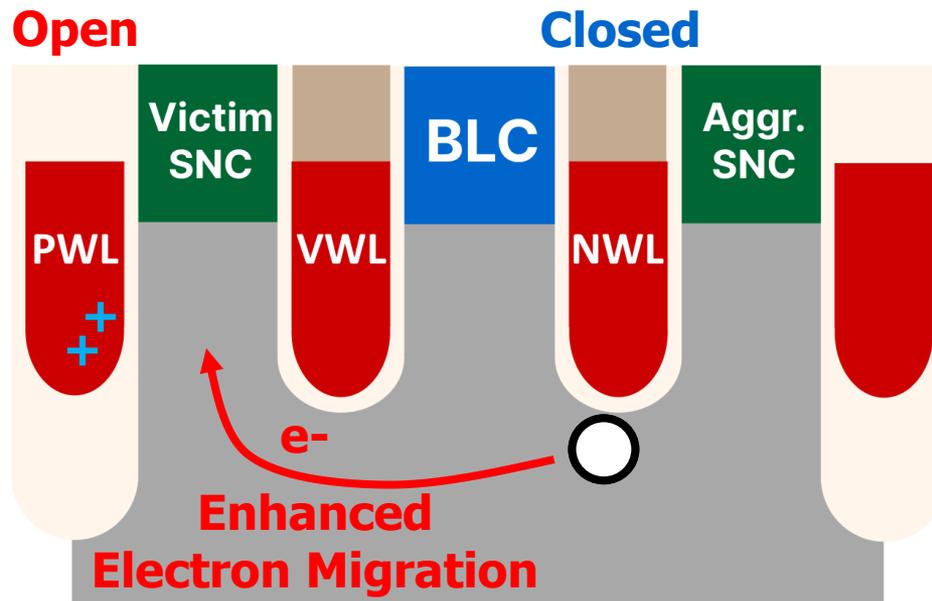
**VWL:** Victim Wordline

**NWL:** Neighboring Wordline (Aggressor)

# Device-Level Mechanism – RowHammer II

## ■ Key Error Mechanisms of RowHammer (Cont'd)

- **Double-Sided RowHammer** is **much more effective** than Single-Sided at inducing bitflips (i.e., require **much fewer aggressor row activations**)
- When NWL is closed, PWL is open: Enhancing electron migration
- NWL is closed for a longer period: More time for electron emission from traps



**PWL:** Passing Wordline (Aggressor)

**VWL:** Victim Wordline

**NWL:** Neighboring Wordline (Aggressor)

# Device-Level Mechanism – RowHammer III

---

## ■ Key Error Mechanisms of RowHammer (Cont'd)

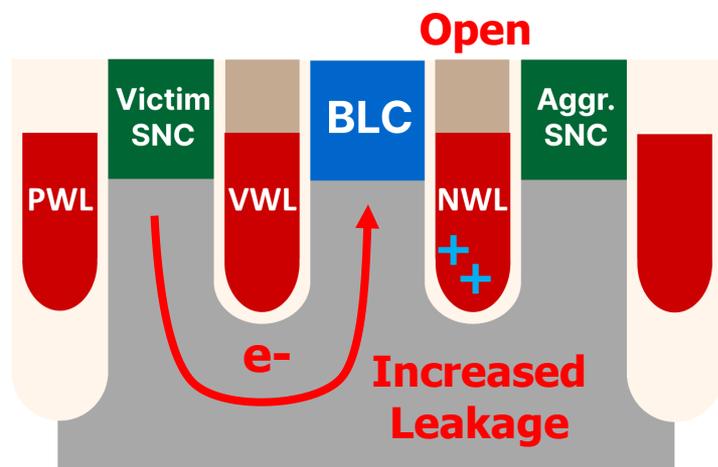
- **Double-Sided RowHammer** is **much more effective** than Single-Sided at inducing bitflips (i.e., require **much fewer aggressor row activations**)
- Electron migration is significantly enhanced by the alternating opening-closing of the NWL and the PWL -> **Enhances 1→0 bitflips**
- State-of-the-art device-level study claim 0→1 bitflips are “eliminated completely” [Zhou+, IRPS'23]

**Key Device-Level Characteristic 1:**  
Double-Sided RowHammer should only induce 1→0 bitflips

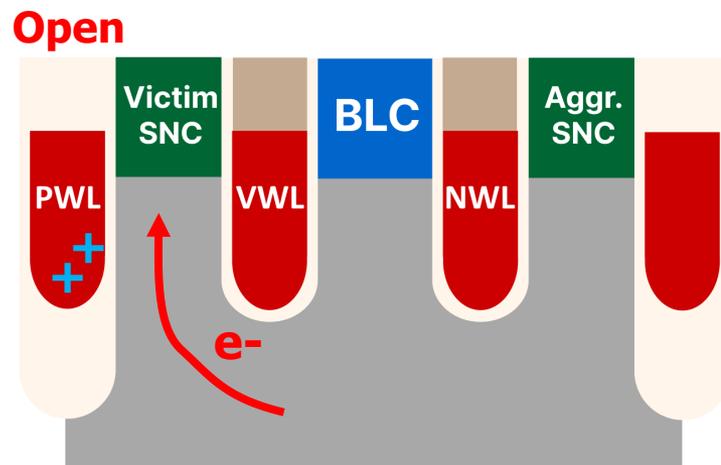
# Device-Level Mechanism – RowPress I

## ■ Key Error Mechanisms of RowPress

- **NWL RowPress:** When NWL is kept open for a long period, its strong electric field increases the leakage from the victim to the BLC, **causing 0→1 bitflips** [Zhou+, TED'24] [Zhou+, IRPS'24]
- **PWL RowPress:** When PWL is kept open for a long period, its strong electric field draws electrons towards the victim, **causing 1→0 bitflips** [Zhou+, TED'24] [Zhou+, IRPS'24]



**NWL RowPress**



**PWL RowPress**

# Device-Level Mechanism – RowPress II

---

## ■ Key Error Mechanisms of RowPress

- **NWL RowPress:** When NWL is kept open for a long period, its strong electric field increases the leakage from the victim to the BLC, **causing 0→1 bitflips** [Zhou+, TED'24] [Zhou+, IRPS'24]
- **PWL RowPress:** When PWL is kept open for a long period, its strong electric field draws electrons towards the victim, **causing 1→0 bitflips** [Zhou+, TED'24] [Zhou+, IRPS'24]

**Key Device-Level Characteristic 2:**  
Single-Sided RowPress should induce both  
1→0 and 0→1 bitflips

# Outline

---

## ■ Background

- Key DRAM Organization
- DRAM Read Disturbance Phenomena: RowHammer & RowPress

## ■ Device-Level DRAM Read Disturbance Mechanisms

## ■ Real-Chip Characterization Methodology

- Reverse Engineering of True- and Anti-Cell Layout

## ■ Real-Chip Characterization Results

- Inconsistency I: Initial Bitflip Direction of Double-Sided RowHammer
- Inconsistency II: Bitflip Count of Double-Sided RowHammer
- Inconsistency III: Bitflip Direction of Single-Sided RowPress

## ■ Hypotheses

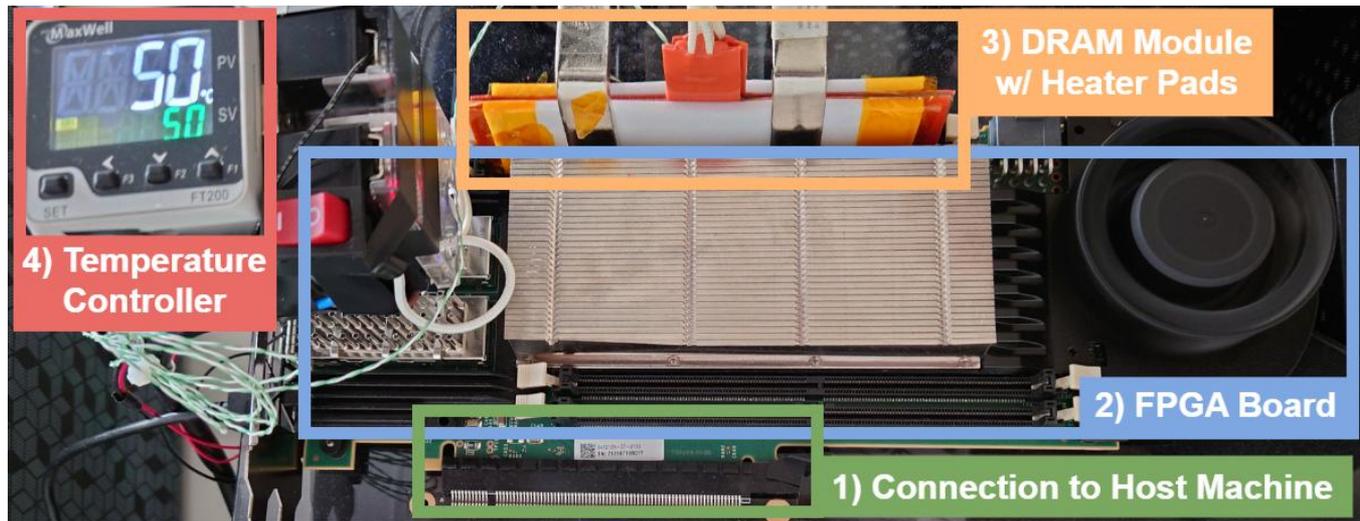
## ■ Conclusion

---

# Real-Chip Characterization Methodology I

## ■ DRAM Bender

- Commodity-off-the-shelf (COTS) DDR4 DRAM testing infrastructure



Fine-grained control over  
DRAM commands and timings (1.5ns granularity)

<https://github.com/CMU-SAFARI/DRAM-Bender>

Olgun et al., "DRAM Bender: An Extensible and Versatile FPGA-based Infrastructure to Easily Test State-of-the-art DRAM Chips," in TCAD, 2023.

# Real-Chip Characterization Methodology II

## ■ DRAM Chips Tested

- COTS DDR4 from all **three major DRAM manufacturers**
- 12 different modules with **different DRAM die revisions and densities**
- 96 DRAM chips in total
- We test 2048 randomly chosen victim rows from each module

Table 1: DRAM Chips Tested

Mfr.	Module Type	Die Density	Die Revision	DQ	Num. Chips	Date Code (YYWW)
S	UDIMM	8 Gb	B	×8	8	1639
S	UDIMM	8 Gb	D	×8	8	2110
S	UDIMM	8 Gb	E	×8	8	2341
S	UDIMM	16 Gb	M	×8	8	2118
S	UDIMM	16 Gb	A	×8	8	2319
S	UDIMM	16 Gb	B	×8	8	2315
S	UDIMM	16 Gb	C	×8	8	2408
H	UDIMM	8 Gb	C	×8	8	2120
H	UDIMM	8 Gb	D	×8	8	1938
H	UDIMM	16 Gb	A	×8	8	2003
H	UDIMM	16 Gb	C	×8	8	2136
M	UDIMM	8 Gb	E	×8	8	2402

# Outline

---

## ■ Background

- Key DRAM Organization
- DRAM Read Disturbance Phenomena: RowHammer & RowPress

## ■ Device-Level DRAM Read Disturbance Mechanisms

## ■ Real-Chip Characterization Methodology

- Reverse Engineering of True- and Anti-Cell Layout

## ■ Real-Chip Characterization Results

- Inconsistency I: Initial Bitflip Direction of Double-Sided RowHammer
- Inconsistency II: Bitflip Count of Double-Sided RowHammer
- Inconsistency III: Bitflip Direction of Single-Sided RowPress

## ■ Hypotheses

## ■ Conclusion

---

# True- and Anti-Cell Layout Reverse Engineering

---

## ■ Motivation

- DRAM internal architecture and layout is opaque to the memory controller
- The observed bitflip direction in real-chip characterization results does not always correspond to the real bitflip direction that happens in the DRAM cells (i.e., due to true- and anti-cells)

## ■ Retention Failure Based Reverse Engineering

- Major DRAM retention leakage paths (junction leakage and GIDL) are **towards the access transistor substrate**, which are usually negatively biased  
[Saino+, IEDM'00] [Yang+, EDL'13] [Park+, IMW'15] [Lee+, JSSC'11]
- Prior works on experimental characterization of DRAM retention failures assume DRAM retention failure **only contain 1→0 bitflips**, and leverages this to reverse engineer the true- and anti-cell layout of DRAM chips  
[Liu+, ISCA'13] [Nam+, ISCA'24]

➤ **We find consistent true- and anti-cell layouts as in prior works**

# Outline

---

## ■ Background

- Key DRAM Organization
- DRAM Read Disturbance Phenomena: RowHammer & RowPress

## ■ Device-Level DRAM Read Disturbance Mechanisms

## ■ Real-Chip Characterization Methodology

- Reverse Engineering of True- and Anti-Cell Layout

## ■ Real-Chip Characterization Results

- Inconsistency I: Initial Bitflip Direction of Double-Sided RowHammer
- Inconsistency II: Bitflip Count of Double-Sided RowHammer
- Inconsistency III: Bitflip Direction of Single-Sided RowPress

## ■ Hypotheses

## ■ Conclusion

---

# Summary of Inconsistencies Found

---

- **Inconsistency I – Double-Sided RowHammer Bitflip Direction**
  - **Real-Chip Characterization:** Observed both  $0 \rightarrow 1$  and  $1 \rightarrow 0$  bitflips;  $0 \rightarrow 1$  bitflips are initially easier to induce than  $1 \rightarrow 0$  bitflips
  - **Device-Level Mechanism:** Double-Sided RowHammer significantly enhances  $1 \rightarrow 0$  leakage that it should only induce  $1 \rightarrow 0$  bitflips
- **Inconsistency II – Double-Sided RowHammer Bitflip Count**
  - **Real-Chip Characterization:** Only with a sufficiently large hammer count does the number of  $1 \rightarrow 0$  bitflips exceed that of  $0 \rightarrow 1$  bitflips
  - **Device-Level Mechanism:** Double-Sided RowHammer significantly enhances  $1 \rightarrow 0$  leakage that it should only induce  $1 \rightarrow 0$  bitflips
- **Inconsistency III – Single-Sided RowPress Bitflip Direction**
  - **Real-Chip Characterization:** Observed overwhelmingly  $1 \rightarrow 0$  bitflips
  - **Device-Level Mechanism:** Single-Sided RowPress should induce both  $0 \rightarrow 1$  and  $1 \rightarrow 0$  bitflips

# Outline

---

## ■ Background

- Key DRAM Organization
- DRAM Read Disturbance Phenomena: RowHammer & RowPress

## ■ Device-Level DRAM Read Disturbance Mechanisms

## ■ Real-Chip Characterization Methodology

- Reverse Engineering of True- and Anti-Cell Layout

## ■ Real-Chip Characterization Results

- Inconsistency I: Initial Bitflip Direction of Double-Sided RowHammer
- Inconsistency II: Bitflip Count of Double-Sided RowHammer
- Inconsistency III: Bitflip Direction of Single-Sided RowPress

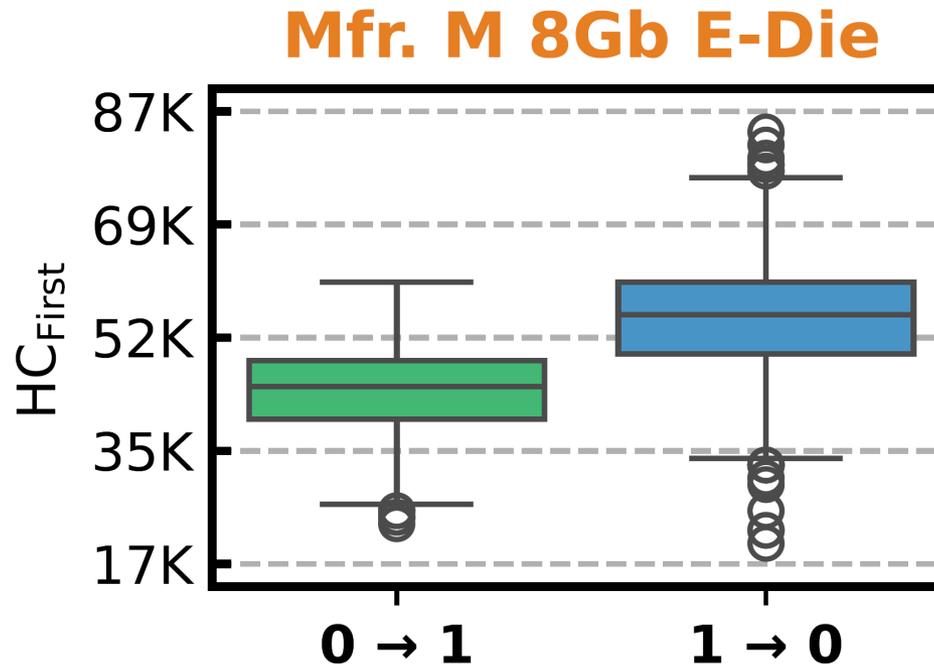
## ■ Hypotheses

## ■ Conclusion

---

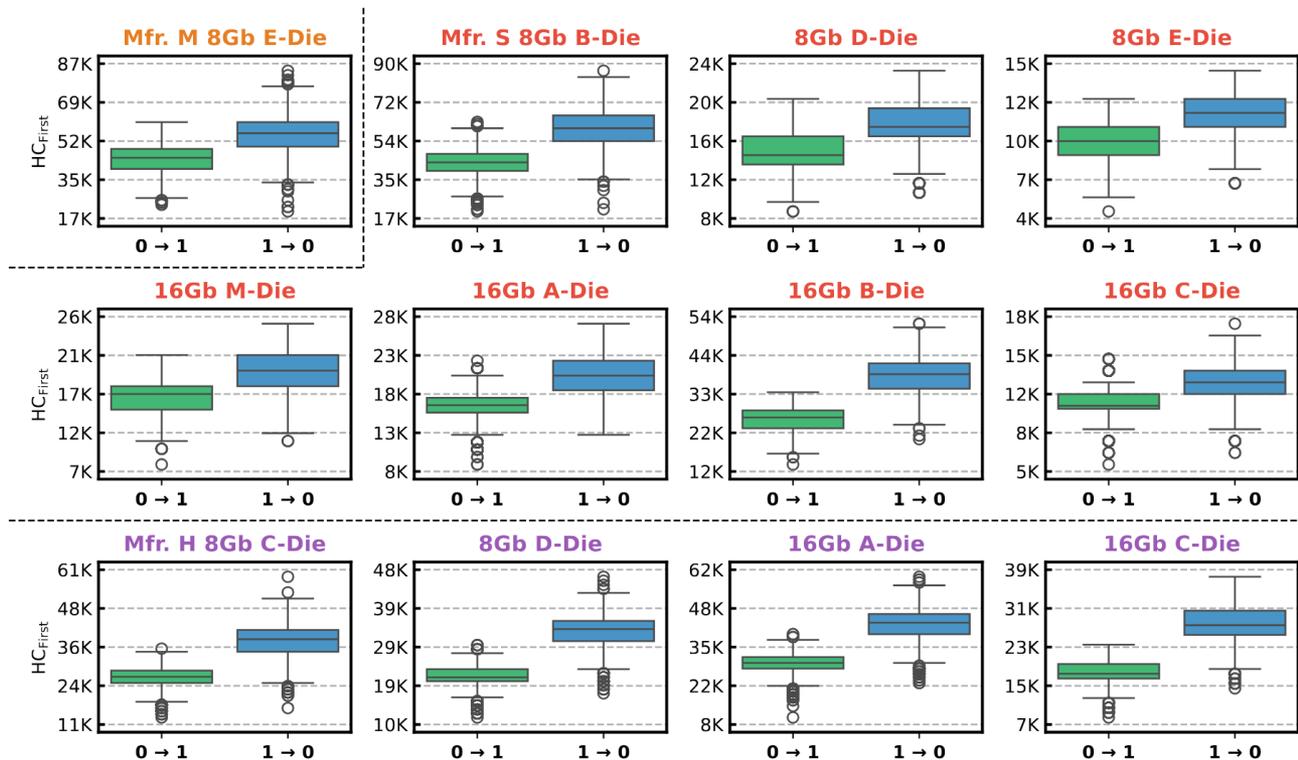
# Initial Bitflip Direction of Double-Sided RowHammer I

- **Access Pattern:** Double-Sided RowHammer
- **Data Pattern:** All physical 1 (or 0) in the victim rows, All physical 0 (or 1) in the aggressor rows
- **Key Metric:**  $HC_{\text{First}}$ , the minimum aggressor row activation (hammer) count to induce at least one bitflip in the victim row



# Initial Bitflip Direction of Double-Sided RowHammer I

- **Access Pattern:** Double-Sided RowHammer
- **Data Pattern:** All physical 1 (or 0) in the victim rows, All physical 0 (or 1) in the aggressor rows
- **Key Metric:**  $HC_{First}$ , the minimum aggressor row activation (hammer) count to induce at least one bitflip in the victim row



# Initial Bitflip Direction of Double-Sided RowHammer II

- Average  $HC_{\text{First}}$  of  $0 \rightarrow 1$  and  $1 \rightarrow 0$  bitflips (Double-Sided RowHammer)

Mfr.	Die Density	Die Revision	Average $HC_{\text{First}}$		Difference	Avg. Difference (Geo. Mean)
			0 to 1	1 to 0		
S	8 Gb	B	43840	59368	26.2%	24.7%
S	8 Gb	D	15398	18041	14.7%	
S	8 Gb	E	9684	11623	16.7%	
S	16 Gb	M	16732	19946	16.1%	
S	16 Gb	A	16981	20942	18.9%	
S	16 Gb	B	26415	38774	31.9%	
S	16 Gb	C	11355	13346	14.9%	
H	8 Gb	C	26500	38440	31.1%	
H	8 Gb	D	22069	33489	34.1%	
H	16 Gb	A	29825	43326	31.2%	
H	16 Gb	C	18042	28041	35.7%	
M	8 Gb	E	44468	55605	20.0%	

**Real-Chip Obsv. 1:** Double-Sided RowHammer induces both  $0 \rightarrow 1$  and  $1 \rightarrow 0$  bitflips

**Real-Chip Obsv. 2:** For Double-Sided RowHammer, it is easier to induce  $0 \rightarrow 1$  bitflips than  $1 \rightarrow 0$  bitflips

# Inconsistency I

---

## ■ **Takeaways from Real-Chip Characterization Results**

- ❑ Double-Sided RowHammer involves error mechanisms for inducing both  $0 \rightarrow 1$  and  $1 \rightarrow 0$  bitflips
- ❑ For Double-Sided RowHammer, the observed error mechanism for  $0 \rightarrow 1$  bitflips is initially stronger than that of  $1 \rightarrow 0$  bitflips in the most vulnerable DRAM cells (i.e., those requiring the least number of aggressor row activations to experience bitflips)

## ■ **Characteristics from Device-Level Mechanisms**

- ❑ Double-Sided RowHammer significantly enhances leakage that causes  $1 \rightarrow 0$  bitflips that it should only induce  $1 \rightarrow 0$  bitflips

# Outline

---

## ■ Background

- Key DRAM Organization
- DRAM Read Disturbance Phenomena: RowHammer & RowPress

## ■ Device-Level DRAM Read Disturbance Mechanisms

## ■ Real-Chip Characterization Methodology

- Reverse Engineering of True- and Anti-Cell Layout

## ■ Real-Chip Characterization Results

- Inconsistency I: Initial Bitflip Direction of Double-Sided RowHammer
- Inconsistency II: Bitflip Count of Double-Sided RowHammer
- Inconsistency III: Bitflip Direction of Single-Sided RowPress

## ■ Hypotheses

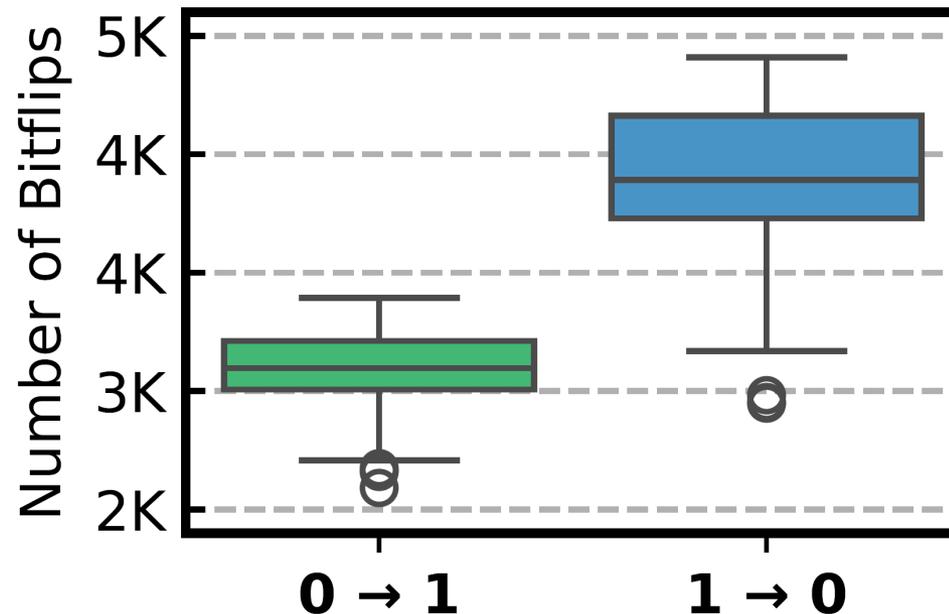
## ■ Conclusion

---

# Bitflip Count of Double-Sided RowHammer I

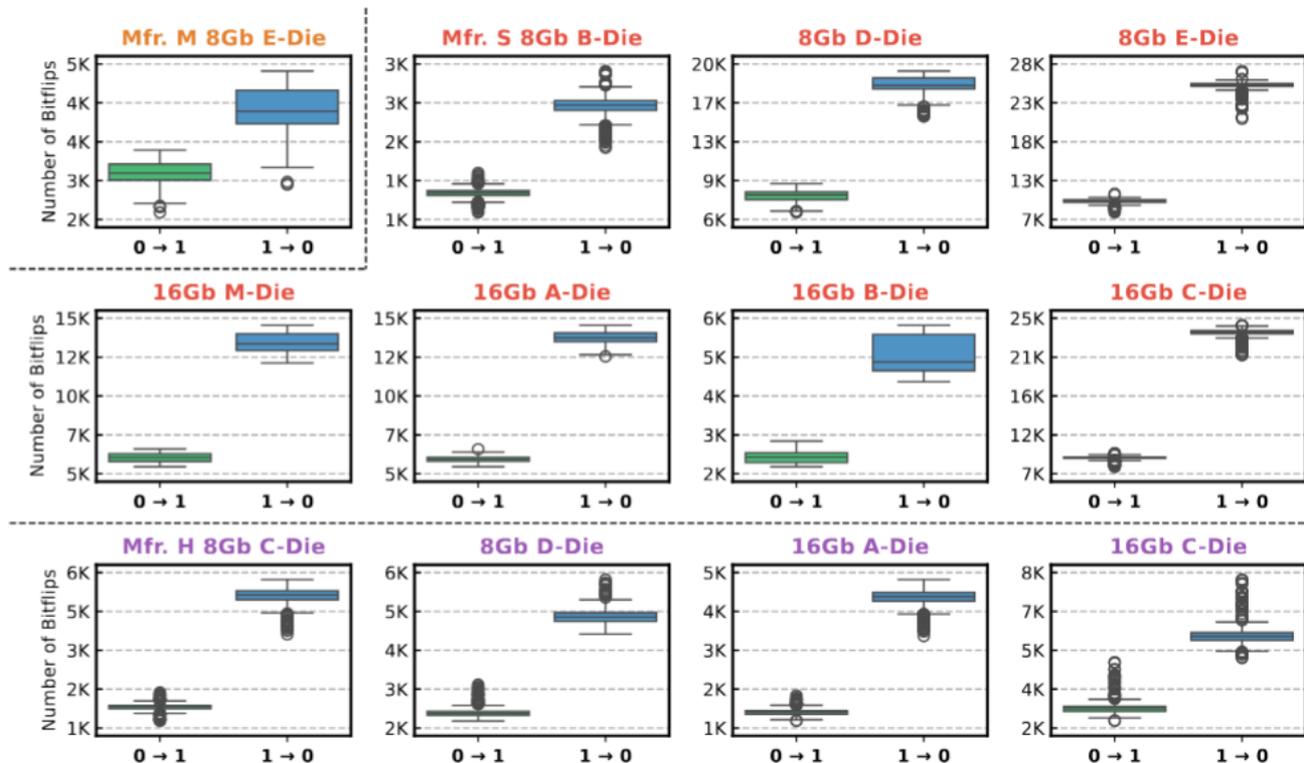
- **Access Pattern:** Double-Sided RowHammer
- **Data Pattern:** All physical 1 (or 0) in the victim rows, All physical 0 (or 1) in the aggressor rows
- **Key Metric: Per-Row Bitflip Count**, after hammering each aggressor row for a sufficiently high number of times (500K)

## Mfr. M 8Gb E-Die



# Bitflip Count of Double-Sided RowHammer I

- **Access Pattern:** Double-Sided RowHammer
- **Data Pattern:** All physical 1 (or 0) in the victim rows, All physical 0 (or 1) in the aggressor rows
- **Key Metric: Per-Row Bitflip Count**, after hammering each aggressor row for a sufficiently high number of times (500K)



# Bitflip Count of Double-Sided RowHammer II

- Average bitflip count (across all victim rows) of 0→1 and 1→0 bitflips (Double-Sided RowHammer)

Mfr.	Die Density	Die Revision	Average Bitflip Count (Across All Rows)		Difference	Avg. Difference (Geo. Mean)
			0 to 1	1 to 0		
S	8Gb	B	1769	3162	78.7%	105.1%
S	8Gb	D	8617	18803	118.2%	
S	8Gb	E	10414	25722	147.0%	
S	16Gb	M	6235	13631	118.6%	
S	16Gb	A	6070	13833	127.9%	
S	16Gb	B	2496	5564	122.8%	
S	16Gb	C	9621	23849	147.9%	
H	8Gb	C	2461	5417	120.1%	
H	8Gb	D	2619	5226	99.5%	
H	16Gb	A	2295	4807	109.4%	
H	16Gb	C	3586	6320	76.2%	
M	8Gb	E	3555	4593	29.2%	

**Real-Chip Obsv. 3:** With sufficiently many hammers, Double-Sided RowHammer induces more 1→0 than 0→1 bitflips

# Bitflip Count of Double-Sided RowHammer III

- **When does the number of 1→0 bitflips start to exceed the number of 0→1 bitflips?**
  - **HC<sub>1→0Exceeds0→1</sub>**: The minimum hammer count that the number of 1→0 bitflips exceed the number of 0→1 bitflips

Mfr.	Die Density	Die Revision	Aggr. Row Act. Count		Difference	Avg. Difference (Geo. Mean)
			HC <sub>First0→1</sub>	HC <sub>1→0Exceeds0→1</sub>		
S	8 Gb	B	43840	241740	451.4%	406.5%
S	8 Gb	D	15398	63198	310.4%	
S	8 Gb	E	9684	31927	229.7%	
S	16 Gb	M	16732	72188	331.4%	
S	16 Gb	A	16981	78820	364.2%	
S	16 Gb	B	26415	153826	482.3%	
S	16 Gb	C	11355	36751	223.6%	
H	8 Gb	C	26500	156087	489.0%	
H	8 Gb	D	22069	141656	541.9%	
H	16 Gb	A	29825	175674	489.0%	
H	16 Gb	C	18042	154951	758.8%	
M	8 Gb	E	44468	235454	429.5%	

# Inconsistency II

---

- **Takeaways from Real-Chip Characterization Results**

- For Double-Sided RowHammer, the observed error mechanism for  $1 \rightarrow 0$  bitflips are only stronger than that of  $0 \rightarrow 1$  bitflips with a sufficiently high hammer count

- **Characteristics from Device-Level Mechanisms**

- Double-Sided RowHammer significantly enhances leakage that causes  $1 \rightarrow 0$  bitflips that it should only induce  $1 \rightarrow 0$  bitflips

# Outline

---

## ■ Background

- Key DRAM Organization
- DRAM Read Disturbance Phenomena: RowHammer & RowPress

## ■ Device-Level DRAM Read Disturbance Mechanisms

## ■ Real-Chip Characterization Methodology

- Reverse Engineering of True- and Anti-Cell Layout

## ■ Real-Chip Characterization Results

- Inconsistency I: Initial Bitflip Direction of Double-Sided RowHammer
- Inconsistency II: Bitflip Count of Double-Sided RowHammer
- Inconsistency III: Bitflip Direction of Single-Sided RowPress

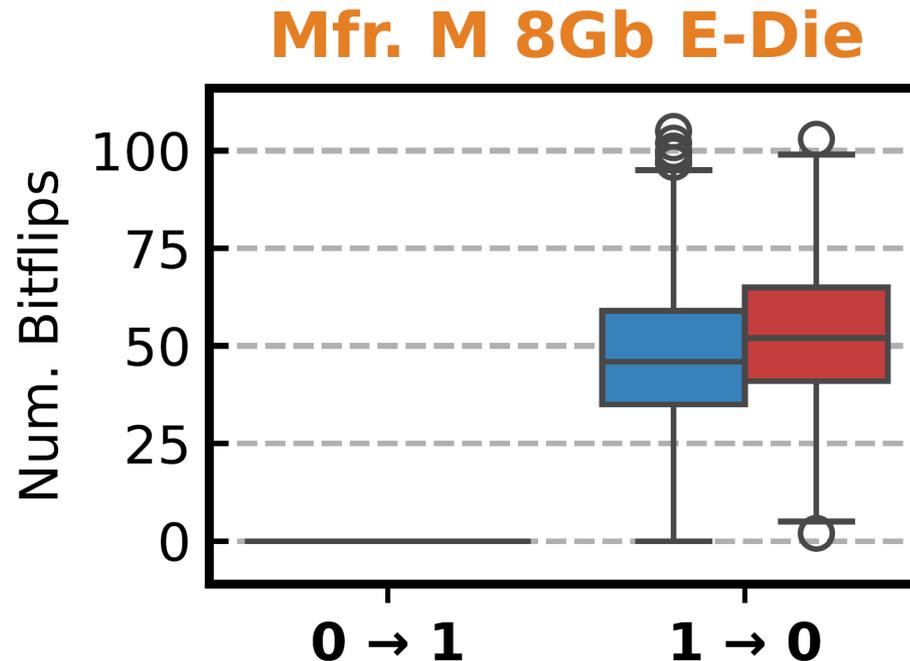
## ■ Hypotheses

## ■ Conclusion

---

# Bitflip Direction of Single-Sided RowPress

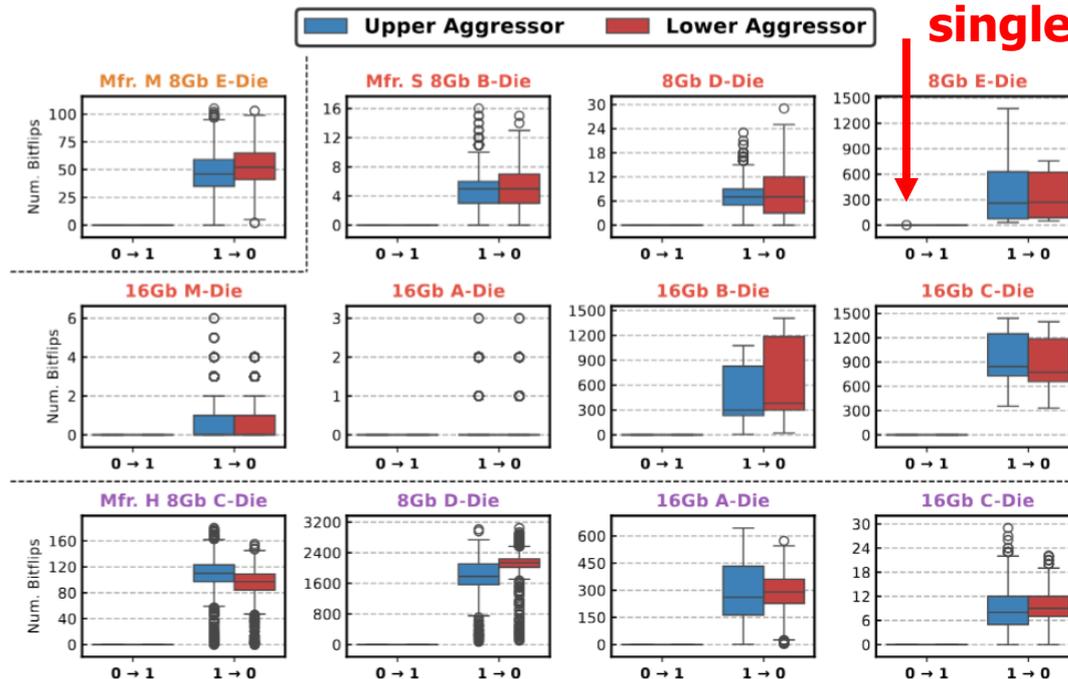
- **Access Pattern:** Single-Sided RowPress at both the upper and lower aggressor row; kept open for  $7.8\mu\text{s}$  per activation
- **Data Pattern:** All physical 1 (or 0) in the victim rows, All physical 0 (or 1) in the aggressor rows
- **Key Metric: Per-Row Bitflip Count**, after activating each aggressor row for a sufficiently high number of times (7500)



# Bitflip Direction of Single-Sided RowPress

- **Access Pattern:** Single-Sided RowPress at both the upper and lower aggressor row; kept open for 7.8 $\mu$ s per activation
- **Data Pattern:** All physical 1 (or 0) in the victim rows, All physical 0 (or 1) in the aggressor rows
- **Key Metric: Per-Row Bitflip Count**, after activating each aggressor row for a sufficiently high number of times (7500)

**Only observed a single 0 $\rightarrow$ 1 bitflip**



# Inconsistency III

---

## ■ **Takeaways from Real-Chip Characterization Results**

- For Single-sided RowPress, for both NWL and PWL, the observed error mechanism for inducing  $1 \rightarrow 0$  bitflips is much stronger than that of  $0 \rightarrow 1$  bitflips that we observe overwhelmingly  $1 \rightarrow 0$  bitflips within the refresh window

## ■ **Characteristics from Device-Level Mechanisms**

- NWL Single-Sided RowPress should induce  $0 \rightarrow 1$  bitflips
- PWL Single-Sided RowPress should induce  $1 \rightarrow 0$  bitflips

# Summary of Inconsistencies Found

---

- **Inconsistency I – Double-Sided RowHammer Bitflip Direction**
  - **Real-Chip Characterization:** Observed both  $0 \rightarrow 1$  and  $1 \rightarrow 0$  bitflips;  $0 \rightarrow 1$  bitflips are initially easier to induce than  $1 \rightarrow 0$  bitflips
  - **Device-Level Mechanism:** Double-Sided RowHammer significantly enhances  $1 \rightarrow 0$  leakage that it should only induce  $1 \rightarrow 0$  bitflips
- **Inconsistency II – Double-Sided RowHammer Bitflip Count**
  - **Real-Chip Characterization:** Only with a sufficiently large hammer count does the number of  $1 \rightarrow 0$  bitflips exceed that of  $0 \rightarrow 1$  bitflips
  - **Device-Level Mechanism:** Double-Sided RowHammer significantly enhances  $1 \rightarrow 0$  leakage that it should only induce  $1 \rightarrow 0$  bitflips
- **Inconsistency III – Single-Sided RowPress Bitflip Direction**
  - **Real-Chip Characterization:** Observed overwhelmingly  $1 \rightarrow 0$  bitflips
  - **Device-Level Mechanism:** Single-Sided RowPress should induce both  $0 \rightarrow 1$  and  $1 \rightarrow 0$  bitflips

# Outline

---

## ■ Background

- Key DRAM Organization
- DRAM Read Disturbance Phenomena: RowHammer & RowPress

## ■ Device-Level DRAM Read Disturbance Mechanisms

## ■ Real-Chip Characterization Methodology

- Reverse Engineering of True- and Anti-Cell Layout

## ■ Real-Chip Characterization Results

- Inconsistency I: Initial Bitflip Direction of Double-Sided RowHammer
- Inconsistency II: Bitflip Count of Double-Sided RowHammer
- Inconsistency III: Bitflip Direction of Single-Sided RowPress

## ■ Hypotheses

## ■ Conclusion

---

# Hypotheses I

---

## ■ Two Possibilities

- The retention failure based true- and anti-cell reverse engineering methodology is not always applicable in modern DRAM chips
- Current device-level explanations of DRAM read disturbance is not comprehensive enough

## ■ Other major retention leakage paths that does NOT leak towards the substrate

- Dielectric leakage that leaks towards BLC?
- More pronounced in modern DRAM as process keeps shrinking [Yu+, ICET'22]

# Hypotheses II

---

- **Existing device-level works make oversimplified assumptions during simulation**
  - Prior works that study the trap-assisted electron migration leakage mechanism only focus on **acceptor-like trap**  
[Yang+, EDL'19] [Walker+, TED'21] [Zhou+, IRPS'23] [Zhou+, TED'24]
  - Are **donor-like traps** really not causing any read disturbance leakage?
- **Device-level simulations focus on a few isolated structures and components**
  - Maybe the modeled read disturbance mechanisms are no longer first-order when put **in the context of a full DRAM array**
  - Other coupling mechanisms between multiple devices and/or process variation might dominate real-chip characterization results
- **Real-chip characterization results are heavily skewed**
  - There could be **asymmetry** between the signal margins of reading a 1 and a 0, as a result of sense amplifier design and operation

# Hypotheses III

---

- **There could be two different sets of read disturbance leakage mechanisms that affects different sets of DRAM cells**
  - For example, the error mechanism of 1→0 bitflips could be **the major mechanism** of Double-Sided RowHammer as prior works study for the majority of the cells
  - However, the error mechanism behind the 0→1 bitflips **determines the tail distribution** of the  $HC_{\text{First}}$  (i.e., it affects the most vulnerable DRAM cells)

# Outline

---

## ■ Background

- Key DRAM Organization & Operation
- DRAM Read Disturbance Phenomena: RowHammer & RowPress

## ■ Device-Level DRAM Read Disturbance Mechanisms

## ■ Real-Chip Characterization Methodology

- Reverse Engineering of True- and Anti-Cell Layout

## ■ Real-Chip Characterization Results

- Inconsistency I: Initial Bitflip Direction of Double-Sided RowHammer
- Inconsistency II: Bitflip Count of Double-Sided RowHammer
- Inconsistency III: Bitflip Direction of Single-Sided RowPress

## ■ Hypotheses

## ■ Conclusion

---

# Conclusion

---

- **Goal:** Align and cross-validate the **experimental characterization** of read disturbance (RowHammer and RowPress) with the error mechanisms modeled by **device-level simulation**
  - **Challenge:** Gap between real-chip characterization and device-level mechanisms due to low-level DRAM array layout (i.e., true- and anti-cells)
- **Key Methodology:**
  - Extract key device-level read disturbance mechanisms from prior works
  - Reverse-engineer the true- and anti-cells layout of real DRAM chips
  - Perform real-chip characterization that directly match the access and data patterns studied in device-level works
- **Key Inconsistencies:**
  - For Double-Sided RowHammer, experimental characterization shows bitflips in both directions while device-level mechanisms suggest only 1→0 bitflips will happen
  - For Single-Sided RowPress, experimental characterization shows overwhelmingly 1→0 bitflips while device-level mechanisms suggest both kinds of bitflips will happen

# Revisiting DRAM Read Disturbance

Identifying Inconsistencies Between  
Experimental Characterization and  
Device-Level Studies

**Haocong Luo**

İsmail Emir Yüksel

Ataberk Olgun

A. Giray Yağlıkçı

Onur Mutlu



**arXiv**

**ETH Zurich**

VTS' 25  
28 April 2025



**Data & Code**

**SAFARI**

**ETH** zürich